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PATENT

Customer No. 22,852

Attorney Docket No. 6082-26

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#5/A
2/5/03
[Signature]

In re Application of:

Tadashi Kokubo et al.

Application No.: 09/936,166

Filed: September 10, 2001

For: Radioactive Microspheres Excellent
in Chemical Durability and Method
for Manufacturing the Same

Group Art Unit: 1617

Examiner: Shahnam J. Sharareh

Commissioner for Patents
Washington, DC 20231

Sir:

AMENDMENT

In response to the Office Action of December 12, 2002, please amend this application as follows:

IN THE CLAIMS:

Please cancel claim 9, amend claim 10, and add new claims 11 and 12 as follows:

10. (Amended) The method according to claim 8, further comprising coating the microsphere with a film after preparing the microsphere and before irradiating with an effective dosage of slow neutrons, the film comprising at least one of the compounds selected from silica (SiO₂), titania (TiO₂), alumina (Al₂O₃), iron (III) oxide (Fe₂O₃), silicon nitride (Si₂N₃, SiN, Si₃N₄), aluminum nitride (AlN), titanium nitride (TiN), iron nitride (Fe₂N, Fe₄N), silicon carbide (SiC) and titanium carbide (TiC).

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Amended

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